WHAT IS CLAIMED IS

5

1. A semiconductor device, comprising: a compound semiconductor substrate having a resistivity less than 1.0×10^8 Ohm-cm at least at surface thereof;

a buffer layer formed on the compound semiconductor substrate and having a super lattice structure; and

an active layer formed on the buffer layer and having an active element formed therein.

15

1.0

 ${\hbox{2. A semiconductor device as claimed in}}$ claim 1, wherein the compound semiconductor substrate has a resistivity less than 0.6 x 10^8 Ohm-cm.

2.5

3. A semiconductor device as claimed in claim 1, wherein the active layer is formed at a position within $5.0~\mu m$ from the surface of the compound semiconductor substrate.

30

4. A semiconductor device as claimed in
claim 1, further comprising an electrode layer formed
on another surface of the compound semiconductor
substrate.

5. A semiconductor device as claimed in claim 4, wherein the electrode layer is not electrically connected to the semiconductor device.

6. A semiconductor device as claimed in claim 4, wherein the electrode layer is connected to one power supply potential of the semiconductor device.

15

7. A semiconductor device as claimed in claim 1, further comprising:

a source electrode and a drain electrode formed on the active layer, separated from each other so as to establish a channel region, and

 $\hbox{a gate electrode formed above the channel} \\ \hbox{region.}$

25

20

8. A semiconductor device as claimed in 30 claim 7, wherein the active layer has 2-Dimentional Electron Gasses.

35

9. A semiconductor device as claimed in claim 1, wherein the active layer comprises: $\hbox{a collector layer of a first conducting} \\$

a base layer of a second conducting type formed on the collector layer;

an emitter layer of the first conducting type formed on the base layer.

10

5

10. A semiconductor device as claimed in claim 1, wherein the compound semiconductor substrate has a resistivity more than 1.0 x 10^8 Ohm-cm in total.

15

11. A semiconductor device as claimed in claim 1, wherein the compound semiconductor substrate comprising a compound semiconductor support substrate having a resistivity more than 1.0 x 10^8 Ohm-cm and a compound semiconductor having a resistivity less than 1.0×10^8 Ohm-cm.